

ADVANCED SILICON SHEET

N87-16411

SURFACE PROPERTY MODIFICATION OF SEMICONDUCTORS BY FLUID ABSORPTION

UNIVERSITY OF ILLINOIS AT CHICAGO

S. Danyluk

Objectives

- . Lubricated Cutting (wafering)
laboratory simulation
mechanism
model
- . Residual Stresses in Sheet
Develop Interferometry Technique
Apply to EFG and WEB

Lubricated Cutting in Simulated Laboratory Experiments

	Surface Morphology
	Hardness
Load, Temperature, Fluids	Wear rate
	Depth of Damage

Mechanism

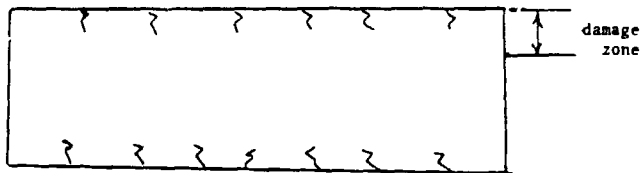
Model



ADVANCED SILICON SHEET

Silicon Wafer

cracks (propagate on
cleavage planes)



plasticity(?)
. due to high compressive stresses
. at crack tips

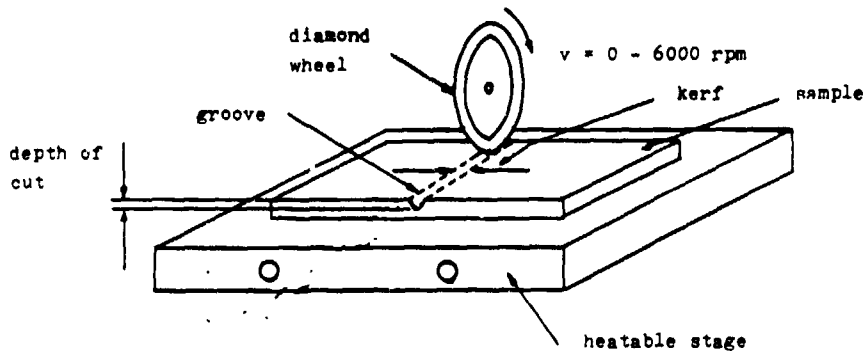
. Simulate Damage

dicing (OD sawing)

indentation (Vickers dia)

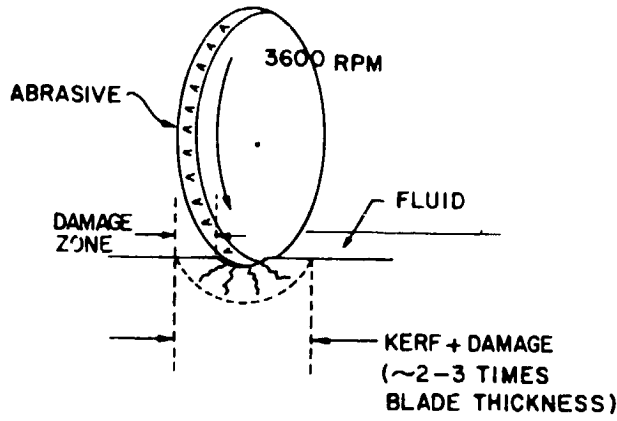
Identify critical parameters

Load
fluid
temperature

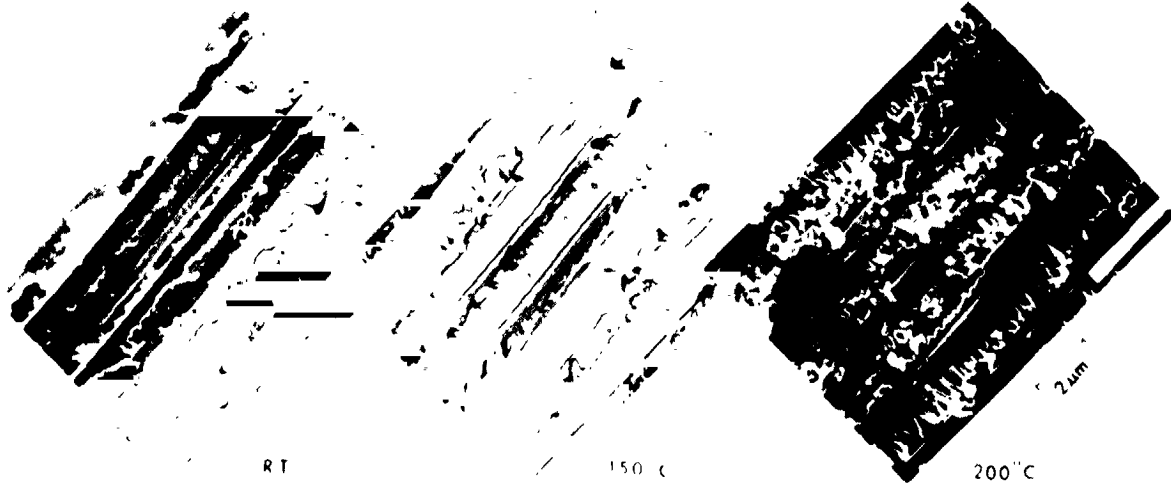
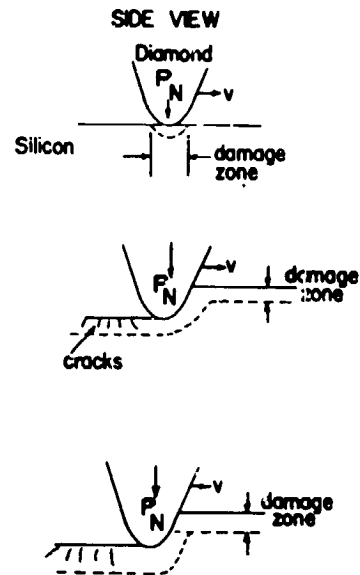
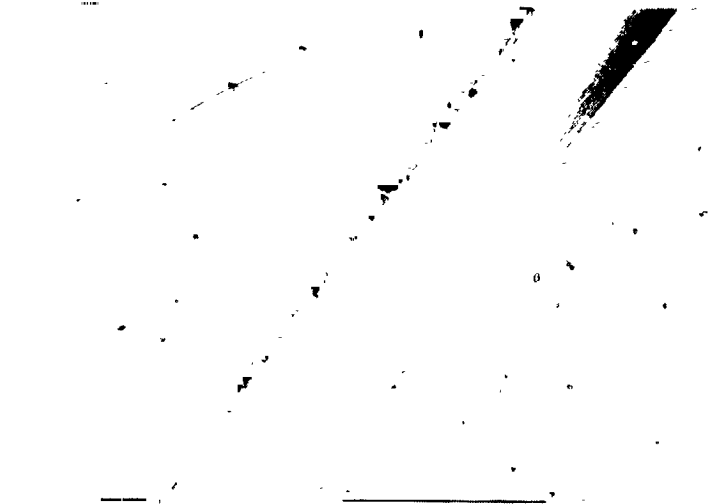


ADVANCED SILICON SHEET

OD Sawing (Dicing)

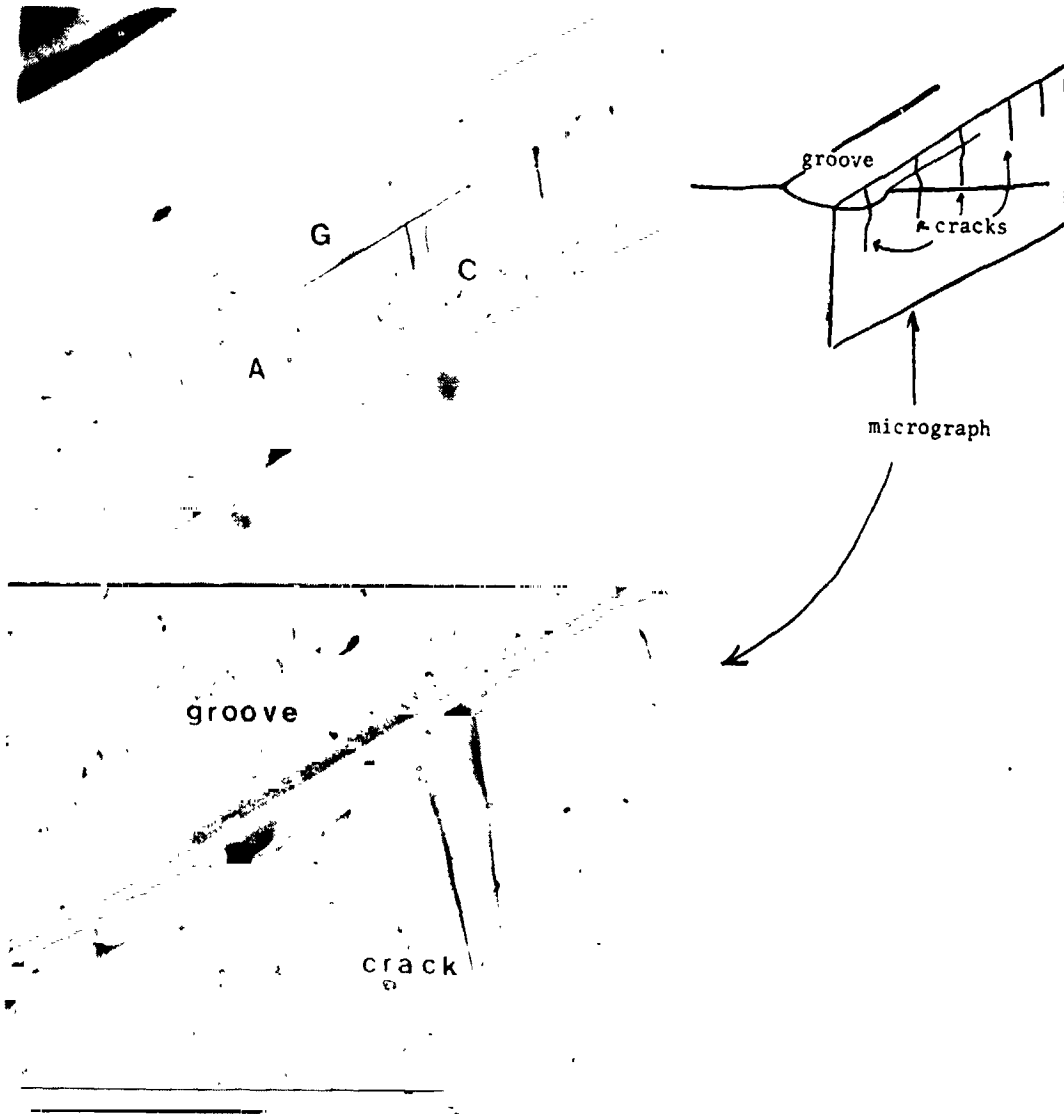


ORIGINAL MANUFACTURER
OF HIGH QUALITY



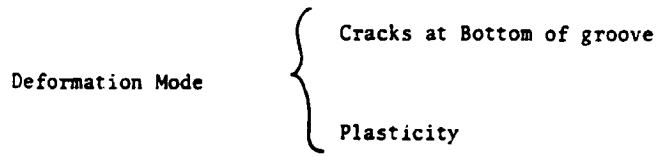
ADVANCED SILICON SHEET

Examples of Cracks at the Bottom of Grooves

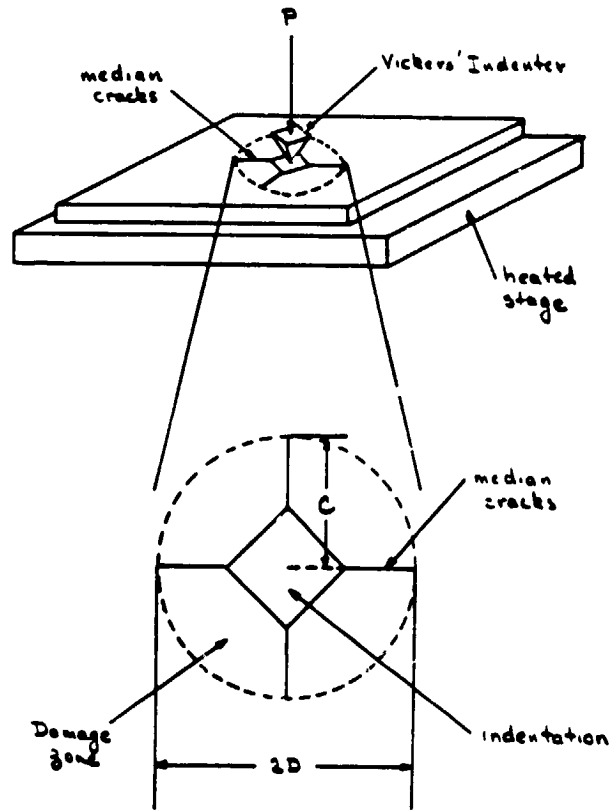


ORIGINAL PAGE IS
OF POOR QUALITY

Summary of High-Speed, Elevated Cutting



Fluids, Temperature--- influence surface morphology



ADVANCED SILICON SHEET

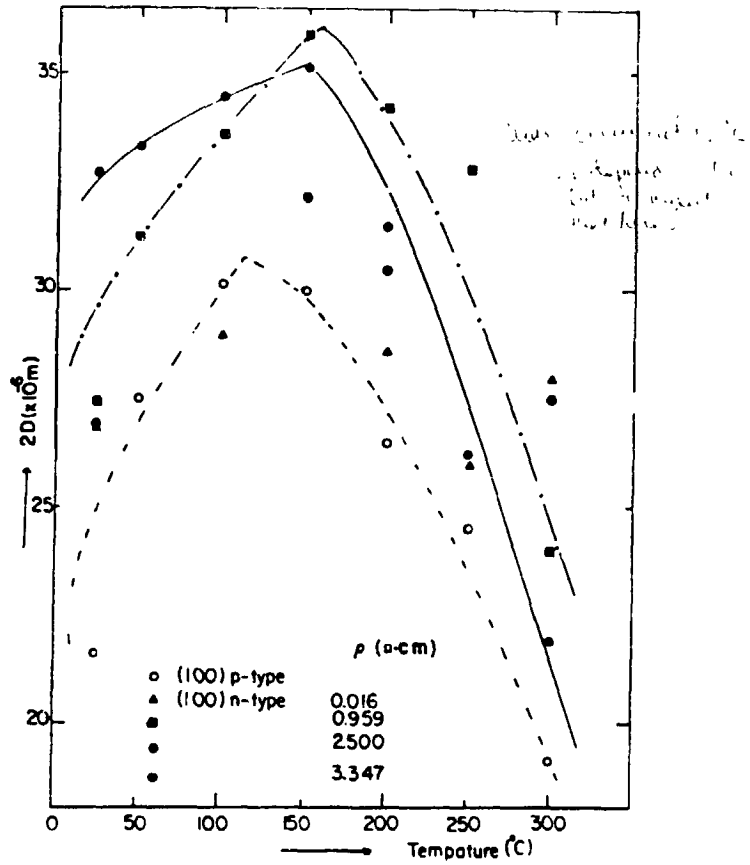
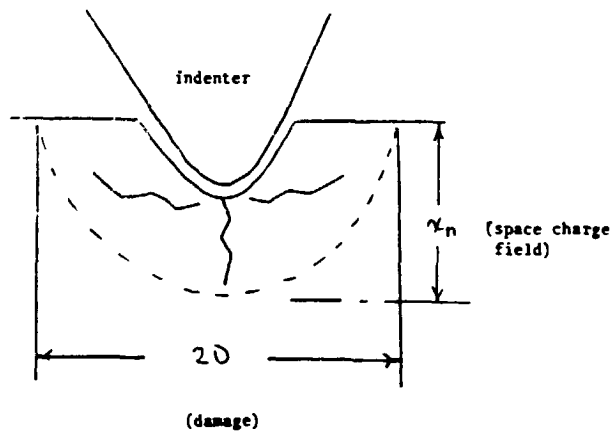


Figure 36. Damage size(2D) vs. indentation temperature for p-type and n-type Cz silicon. The indentation load was 0.49N. The n-type silicon had resistivities of 0.016, 0.959, 2.5, and 3.347 Ω-cm.

Indentation Model



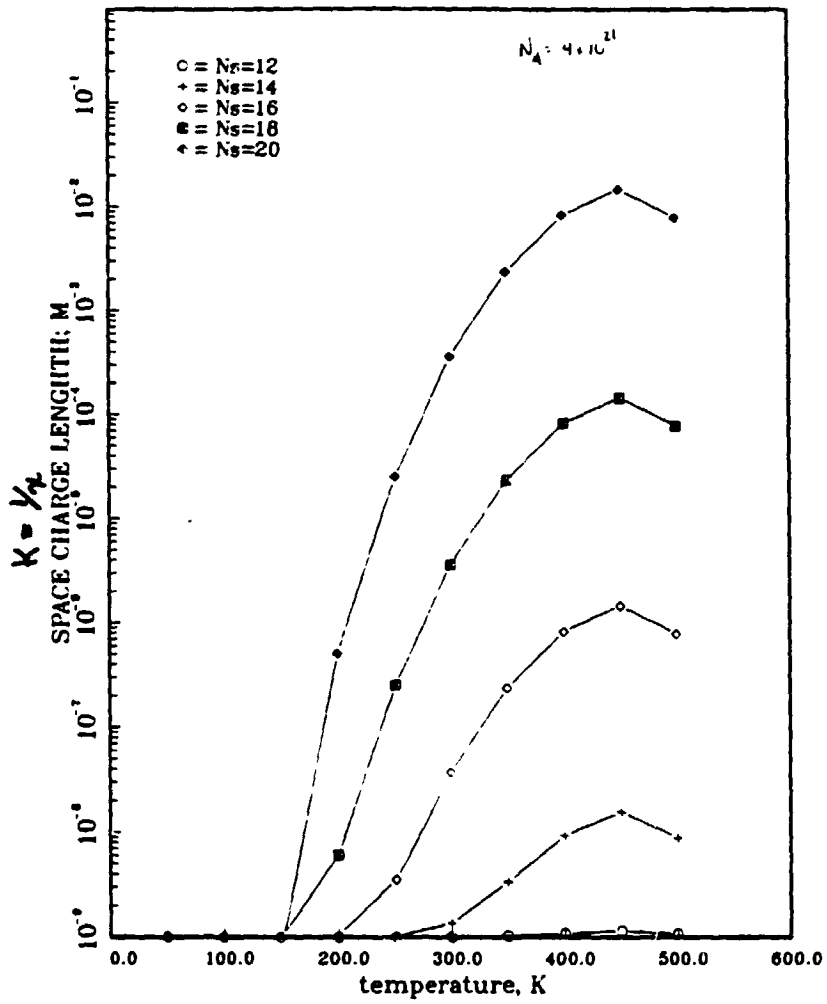
$2D \propto X_n$	at low P, space charge fields influence damage
------------------	--

$$X_n = \frac{N_s}{N_D} \left[\frac{e \frac{(\mu_e - E_{SS})}{kT}}{1 + e \frac{(\mu_e - E_{SS})}{kT}} - 1 \right]$$

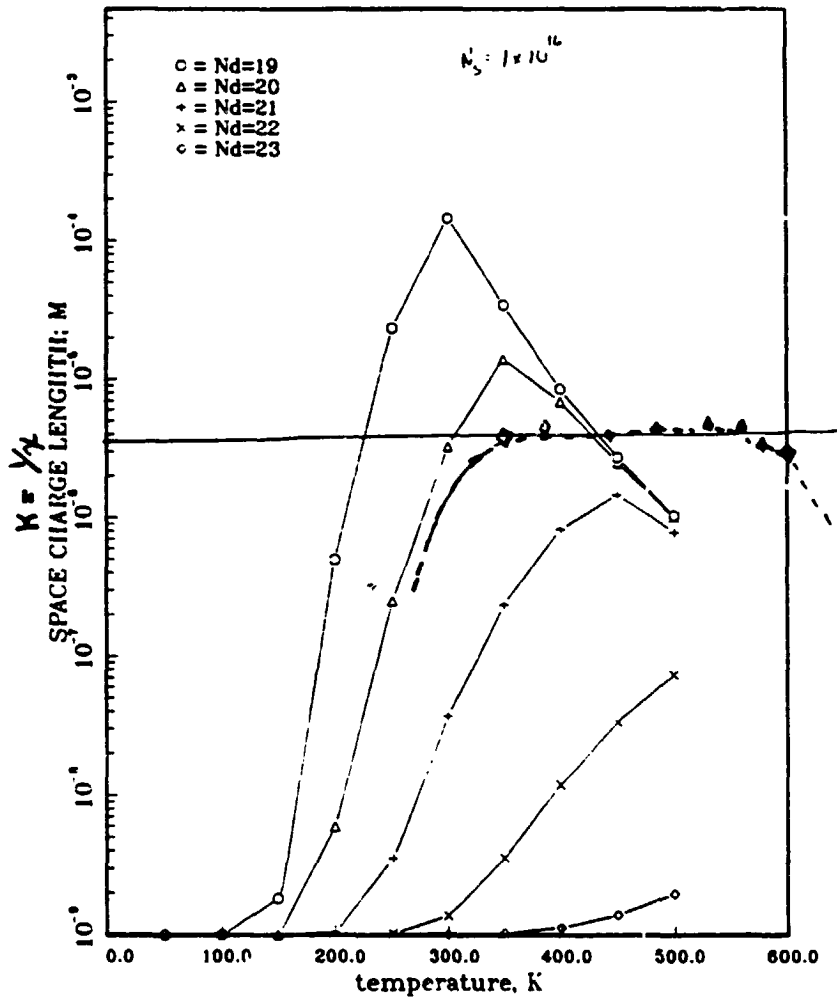
- *N_s - finite number of surface states
- *N_s, E_{SS} not known but extracted from expt.
- *μ_e, electrochemical potential

$$2D = f(N_D, N_s, E_{SS}, T)$$

Space Charge Length as a Function of Temperature



Space Charge Length as a Function of Temperature



ADVANCED SILICON SHEET

Summary of Indentation Model

2D and x_n exhibit maximum at 150C

$$N_s = 10^{16} - 10^{18} / m^2$$

$$E_s = 0.79 \text{ eV}$$

Doping level influences 2D

Predict T, N_D variation with 2D

Summary of Silicon Results

. Wear rate

. Ethanol - highest

. air - lowest

. Damage

.load — plasticity, p 100gf
 — cracks, p 200gf

.temp

cracks, damage decreases
at T 250°C

. bulk doping

. fluid

Conclusions

Mechanisms of Wear

- . Wear rate and damage includes: cracks and plasticity
- . Laboratory simulation tests provide guidance in modifying industrial practices.
- . Wear rate may be optimized and damage may be minimized

Load (below 0.98N (100fg)
Fluid (alcohol-based vs. water-based fluids)
Temp (200-300°C)

- . Model allows parameters to be identified and range to be extrapolated.
- . Unresolved problems: Impact, fatigue

Residual Stresses

- . Interferometry is a promising NDT technique for sheet geometries
- . Edges - compressive
Center - tensile
- . EFG - $v_{\text{growth}} = 2 \text{ cm/min} - \sigma_{\text{RS}} = \pm 10 \text{ MPa}$
WEB - $v_{\text{growth}} = \text{ cm/min} - \sigma_{\text{RS}} = \pm 1 \text{ MPa}$
- . Unresolved problems: anisotropy of E, ν
dendrite geometry